



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Patent Application of

Helen H. ZHU et al.

Application No.: 09/820,694

Filing Date: March 30, 2001

Title: METHOD OF PLASMA ETCHING SILICON NITRIDE

Group Art Unit: 2823

Examiner: Julio J. Maldonado

Confirmation No.: 7374

PETITION FOR EXTENSION OF TIME

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

The following extension of time is requested to: respond to Office Action dated June 9, 2004.

one month to October 9, 2004 ☐ \$55.00 (2251) ☒ \$110.00 (1251)

☐ The shortened statutory period has been reset by an Advisory Action dated \_\_\_\_\_.

☐ An extension fee in the amount of \_\_\_\_\_ is enclosed.

☒ Charge \$ 110.00 to Deposit Account No. 02-4800.


☐ Charge \_\_\_\_\_ to credit card. Form PTO-2038 is attached.

The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. §§1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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Date: October 12, 2004

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01 FC:1251 110.00 DA  
~~02 FC:1202 100.00 DA~~